

## Effects of Voltage Pulse Characteristics on Some Performance Parameters of $\text{Li}_x\text{CoO}_2$ -based Resistive Switching Memory Devices

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**Abstract :** In the field of Nanoelectronics, a major research activity is being developed towards non-volatile memories. To face the limitations of existing Flash memory cells (endurance, downscaling, rapidity...), new approaches are emerging, among them resistive switching memories (Re-RAM). In this work, we analysed the behaviour of  $\text{Li}_x\text{CoO}_2$  oxide thin films in electrode/film/electrode devices. Preliminary results have been obtained concerning the influence of bias pulses characteristics (duration, value) on some performance parameters, such as endurance and resistance ratio (ROFF/RON). Besides, Conducting Probe Atomic Force Microscopy (CP-AFM) characterizations of the devices have been carried out to better understand some causes of performance failure, and thus help optimizing the switching performance of such devices.

**Keywords :** non volatile resistive memories, resistive switching, thin films, endurance

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